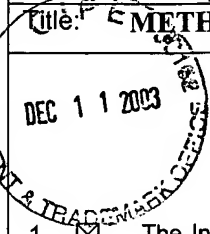


<b>TRANSMITTAL OF INFORMATION DISCLOSURE STATEMENT</b> <b>Under 37 CFR 1.97(b), (c), or (d)</b>			Docket No. <b>6716/ETCH/SILICON/JB</b>
In re Application of: <b>Davis, et al.</b>			
Serial No. <b>10/674,568</b>	Filing Date <b>September 29, 2003</b>	Examiner	Group Art Unit
Title: <b>METHOD AND SYSTEM FOR MONITORING AN ETCH PROCESS</b>			
Address to: <b>Commissioner for Patents</b> <b>Alexandria, VA 22313-1450</b>			



**37 CFR 1.97(b)**

1. ☒ The Information Disclosure Statement submitted herewith is being filed within three months of the filing of a national application other than a continued prosecution application under 37 CFR 1.53(d); within three months of the date of entry of the national stage as set forth in 37 CFR 1.491 in an international application; before the mailing of a first Office Action on the merits; or before the mailing of a first Office Action after the filing of a request for continued examination under 37 CFR 1.114.

**37 CFR 1.97(c)**

2. ☐ The Information Disclosure Statement submitted herewith is being filed after the period specified in 37 CFR 1.97(b), but prior to the mailing date of a Final Action under 37 CFR 1.113, a Notice of Allowance under 37 CFR 1.311, or an Action that otherwise closes prosecution in the application, and is accompanied by the statement or fee as indicated below.

**37 CFR 1.97(d)**

3. ☐ The Information Disclosure Statement submitted herewith is being filed after the period specified in 37 CFR 1.97(c), but on or before payment of the issue fee and is accompanied by the statement and fee as indicated below.

**Required Statements and/or Fees Under 37 CFR 1.97(c) or (d)**

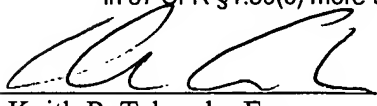
☐ Each item of information contained in the accompanying Information Disclosure Statement was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of the Information Disclosure Statement. (37 CFR 1.97(e)(1))

☐ No item of information in the accompanying Information Disclosure Statement was cited in a communication from a foreign patent office in a counterpart foreign application, and, to the knowledge of the undersigned person, after making reasonable inquiry, no item of information contained in the accompanying Information Disclosure Statement was known to any individual designated in 37 CFR 1.56(c) more than three months prior to the filing of the Information Disclosure Statement. (37 CFR 1.97(e)(2))

☐ The fee set forth in 37 CFR 1.17(p). Please credit any overpayment or charge any insufficiencies to deposit account number 20-0782.

**37 CFR §1.704(d)**

4. ☐ Each item of information in the accompanying Information Disclosure Statement was cited in a communication from a foreign patent office in a counterpart application and this communication was not received by any individual designated in 37 CFR §1.56(c) more than thirty days prior to the filing of the Information Disclosure Statement.

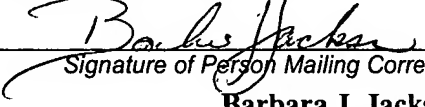


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Dated: DEC 5, 2003

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I certify that this document is being deposited on 12-5-2003 with the U.S. Postal Service as first class mail under 37 CFR §1.8 and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450

  
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**Barbara J. Jackson**  
 Typed or Printed Name of Person Mailing Correspondence

U.S. Department of Commerce, Patent and Trademark Office (PTO Form 1449 modified)					Docket No. 6716/ETCH/SILICON/JB		Serial No. 10/674,568	
<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>					Applicant Davis, et al.		Confirmation No.:	
(Use several sheets if necessary)					Filing Date September 29, 2003		Group	
Examiner								
<b>U.S. Patent Documents</b>								
*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate	
	A1	4,767,496	08/30/1988	Hieber	156	627		
	A2	5,798,529	08/25/1998	Wagner	250	492.2		
	A3	5,926,690	07/20/1999	Toprac et al.	438	17		
	A4	5,948,203	09/07/1999	Wang	156	345		
	A5	6,004,706	12/21/1999	Ausschnitt et al.	430	30		
	A6	6,027,842	02/22/2000	Ausschnitt et al.	430	30		
	A7	6,161,054	12/12/2000	Rosenthal et al.	700	121		
	A8	6,245,581	06/12/2001	Bonser et al.	438	8		
	A9	6,424,417	07/23/2002	Cohen et al.	356	388		
	A10	6,486,492	11/26/2002	Su	257	48		
	A11	2002/0171828	11/21/2002	Cohen et al.	356	328	07/01/2002	
<b>Foreign Patent Documents</b>								
*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
							YES	NO
	B1						<input type="checkbox"/>	<input type="checkbox"/>
	B2						<input type="checkbox"/>	<input type="checkbox"/>
<b>OTHER ART</b>								
*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.						
	C1	Lee, et al., "Analysis of Reflectometry and Ellipsometry Data from Patterned Structures," Characterization and Metrology for UCSI Technology: 1998 International Conference, Seiler, et al., eds., pg 331-335						
	C2	Raymond, "Angle-resolved scatterometry for semiconductor manufacture," Microlithography World, Winter 2000.						
	C3	Toprac, A., "AMD's Advanced Process Control of Ply-Gate Critical Dimension," Proc. SPIE Vol 3882, pg 62-65, Sept, 1999.						
	C4	Yang, et al., "Line-profile and Critical Dimension Measurements Using a Normal Incidence Optical Metrology System," Proceedings of SPIE Vol. 4689, March 2002,						
Examiner					Date Considered			
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.								